


CERTIFICATE OF TRANSMISSION BY FACSIMILE (37 CFR 1.8)			Docket No. BU9-99-197
Applicant(s): Furukawa et al.			
Application No. 09/599,783	Filing Date 6/22/2000	Examiner Julio J. Maldonado	Group Art Unit 2823
Invention: METHOD FOR ETCHING A SEMICONDUCTOR SUBSTRATE USING GERMANIUM HARD MASK			
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In re Application: Furukawa, et al

Group Art Unit: 2823

Serial No.: 09/599,783

Examiner: Julio J. Maldonado

Filed: 06/22/2000

Docket No.: BU9-99-197

Title: Method For Etching A Semiconductor Substrate Using Germanium Hard Mask

Commissioner for Patents
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Request for Reconsideration

Sir:

This Request for reconsideration is in response to the Notice of Drawing Inconsistency with Specification mailed November 29, 2004.

In the Specification

Please add the following text between lines 19 and 20 of page 3:

FIG. 7 depicts FIG. 6 after portions of the substrate in FIG. 6 have been etched, in accordance with the present invention.

FIG. 8 depicts a semiconductor device that may be formed on the substrate of FIG. 7, in accordance with the present invention.

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